



US00D586050S

(12) **United States Design Patent**
Chen

(10) **Patent No.:** **US D586,050 S**

(45) **Date of Patent:** **** Feb. 3, 2009**

(54) **MASK**

(76) **Inventor:** **Chun-Nan Chen**, 182, Haichung St., An Nan District, Tainan (TW)

(**) **Term:** **14 Years**

(21) **Appl. No.:** **29/297,854**

(22) **Filed:** **Nov. 20, 2007**

(51) **LOC (9) Cl.** **29-02**

(52) **U.S. Cl.** **D29/110**

(58) **Field of Classification Search** D29/102-112, D29/122; D24/110.1-110.4, 191; 267/142-146, 267/113, 64.13; 2/410-414, 416, 422-425, 2/9, 10, 206, 427, 429, 5, 6.3, 6.5, 6.7; 128/857-858
See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

D407,858 S *	4/1999	Cyr et al.	D29/108
D518,605 S *	4/2006	Chen	D29/108
D522,697 S *	6/2006	Chen	D29/108
D526,094 S *	8/2006	Chen	D29/108
D529,234 S *	9/2006	Broersma	D29/108

D555,837 S *	11/2007	Chen	D29/110
D570,551 S *	6/2008	Broersma	D29/108
2006/0090234 A1 *	5/2006	Cyr	2/9
2007/0050896 A1 *	3/2007	Stevens	2/427
2008/0086795 A1 *	4/2008	Cyr et al.	2/425

* cited by examiner

Primary Examiner—Ruth McInroy

(74) *Attorney, Agent, or Firm*—Alan Kamrath; Kamrath & Associates PA

(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask showing my design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a rear elevational view thereof;

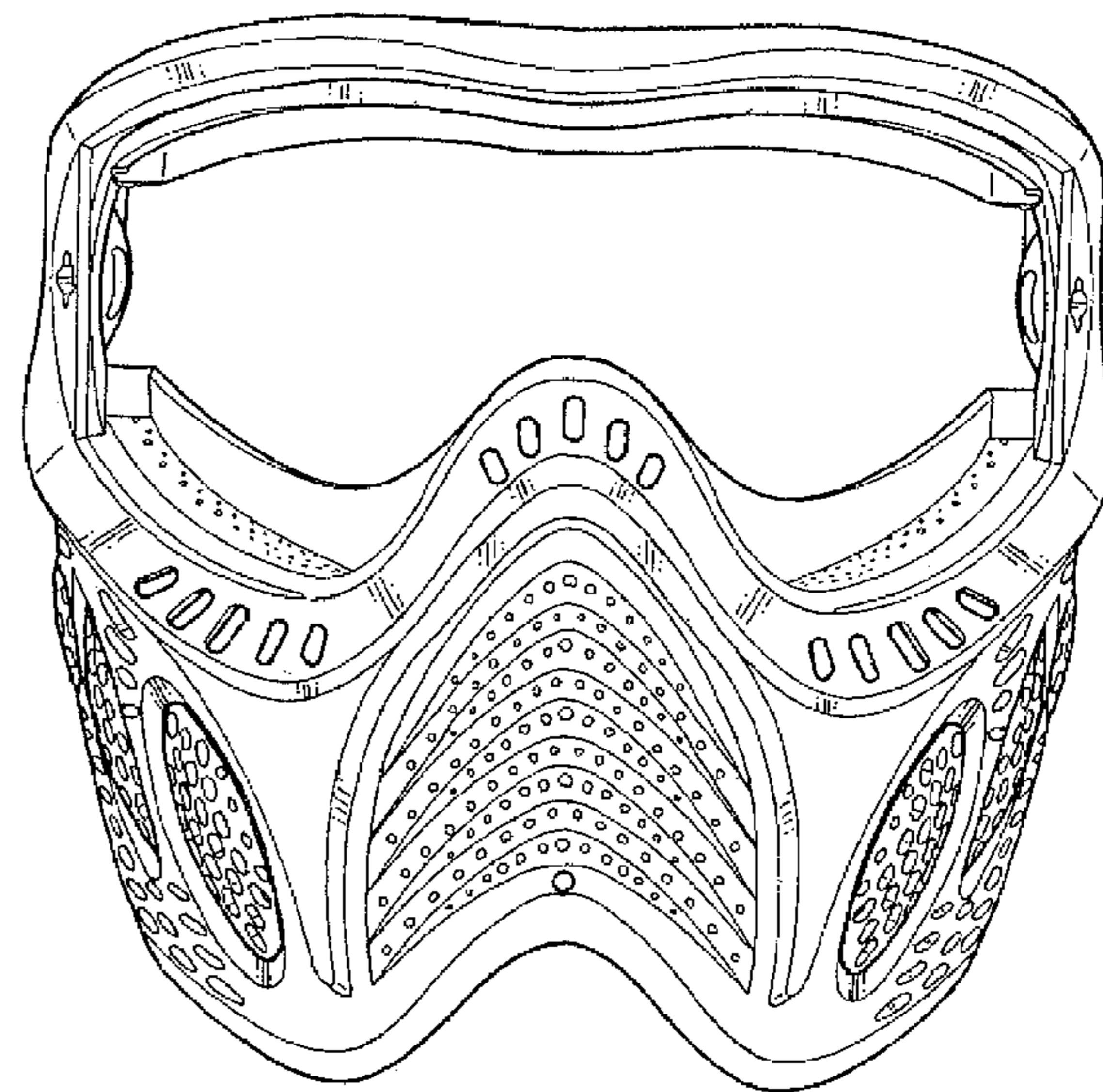
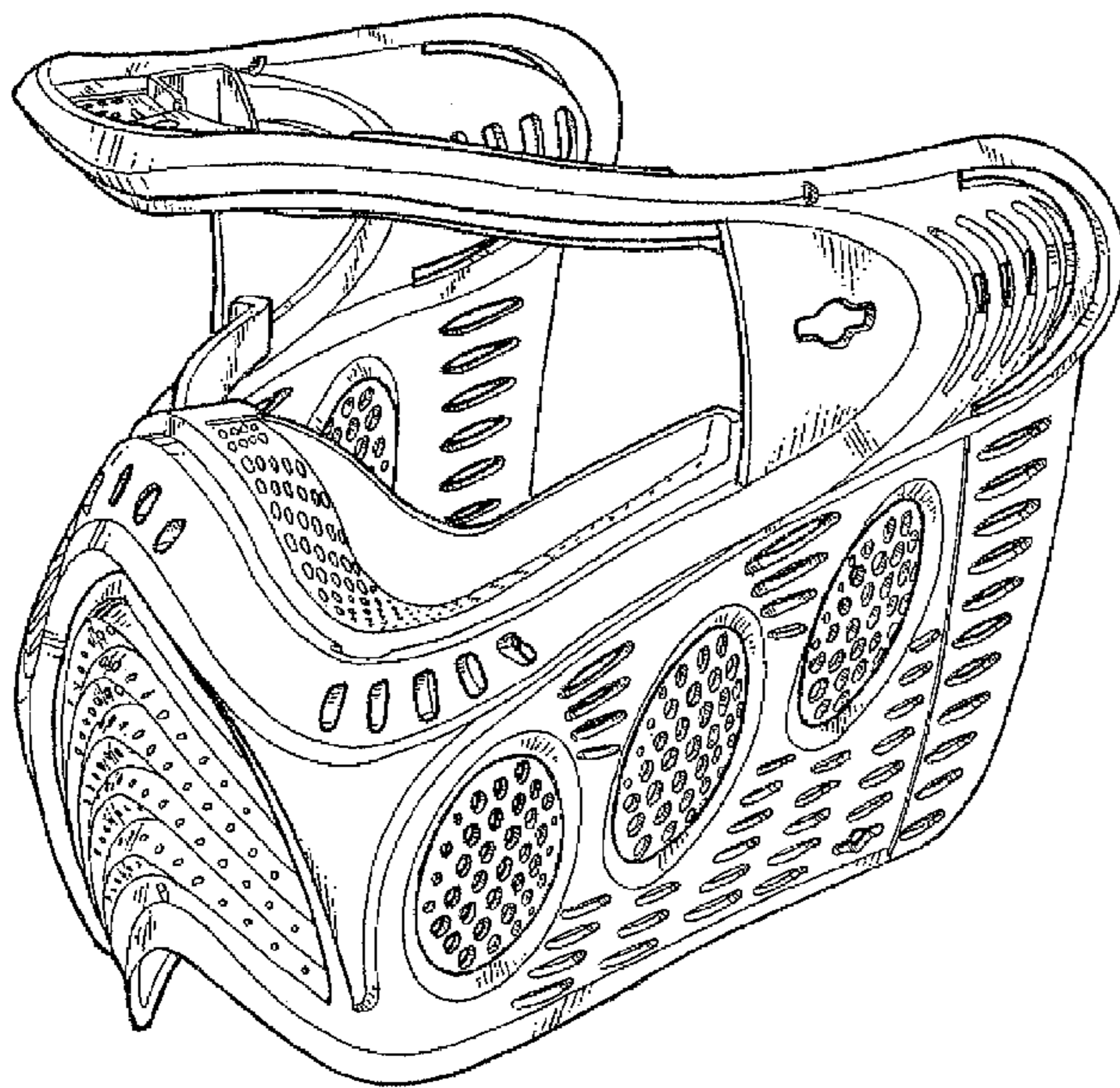
FIG. 4 is a left side elevational view thereof;

FIG. 5 is a right side elevational view thereof;

FIG. 6 is a top plan view thereof; and,

FIG. 7 is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



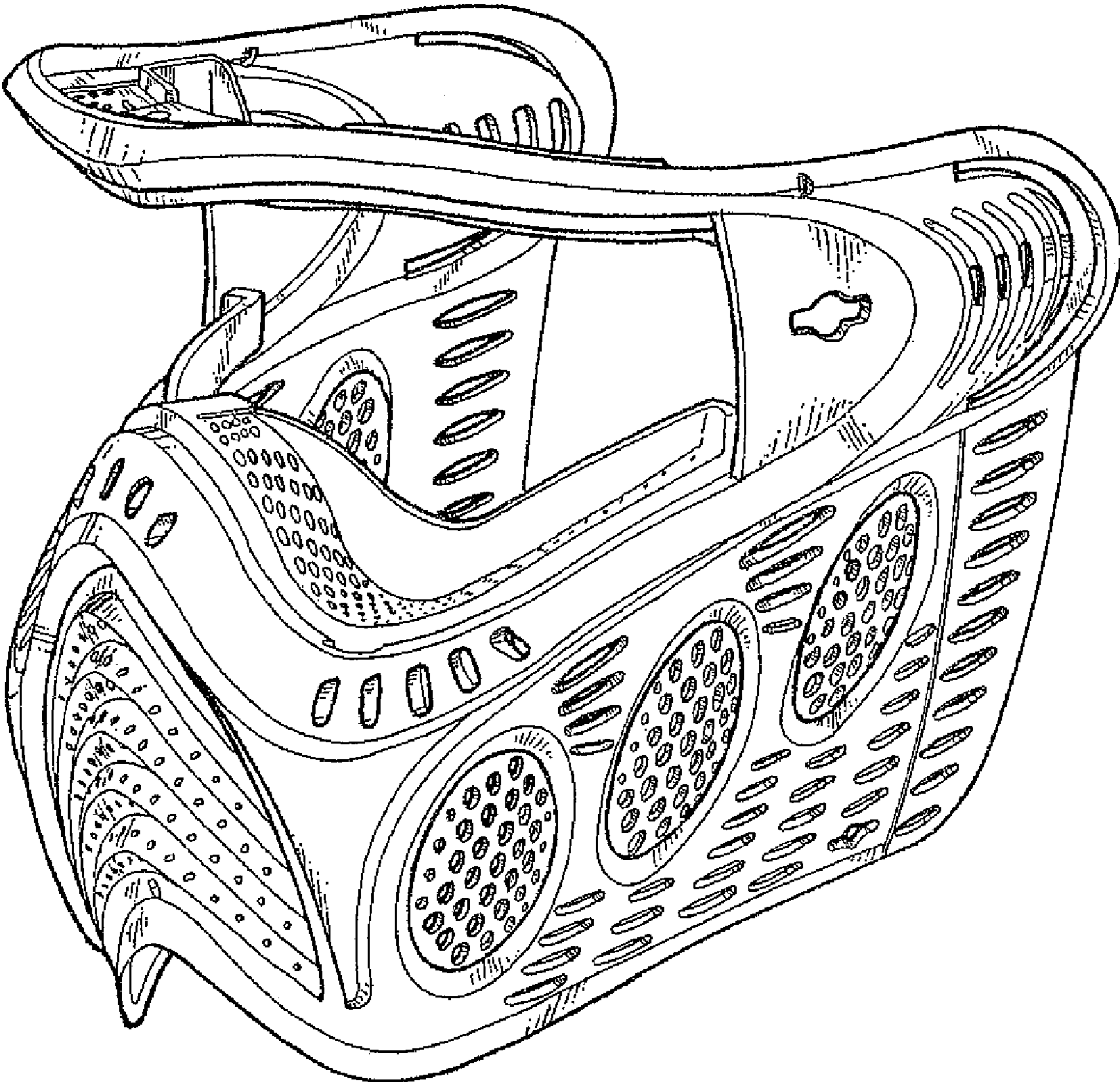


FIG.1



FIG.2



FIG.3

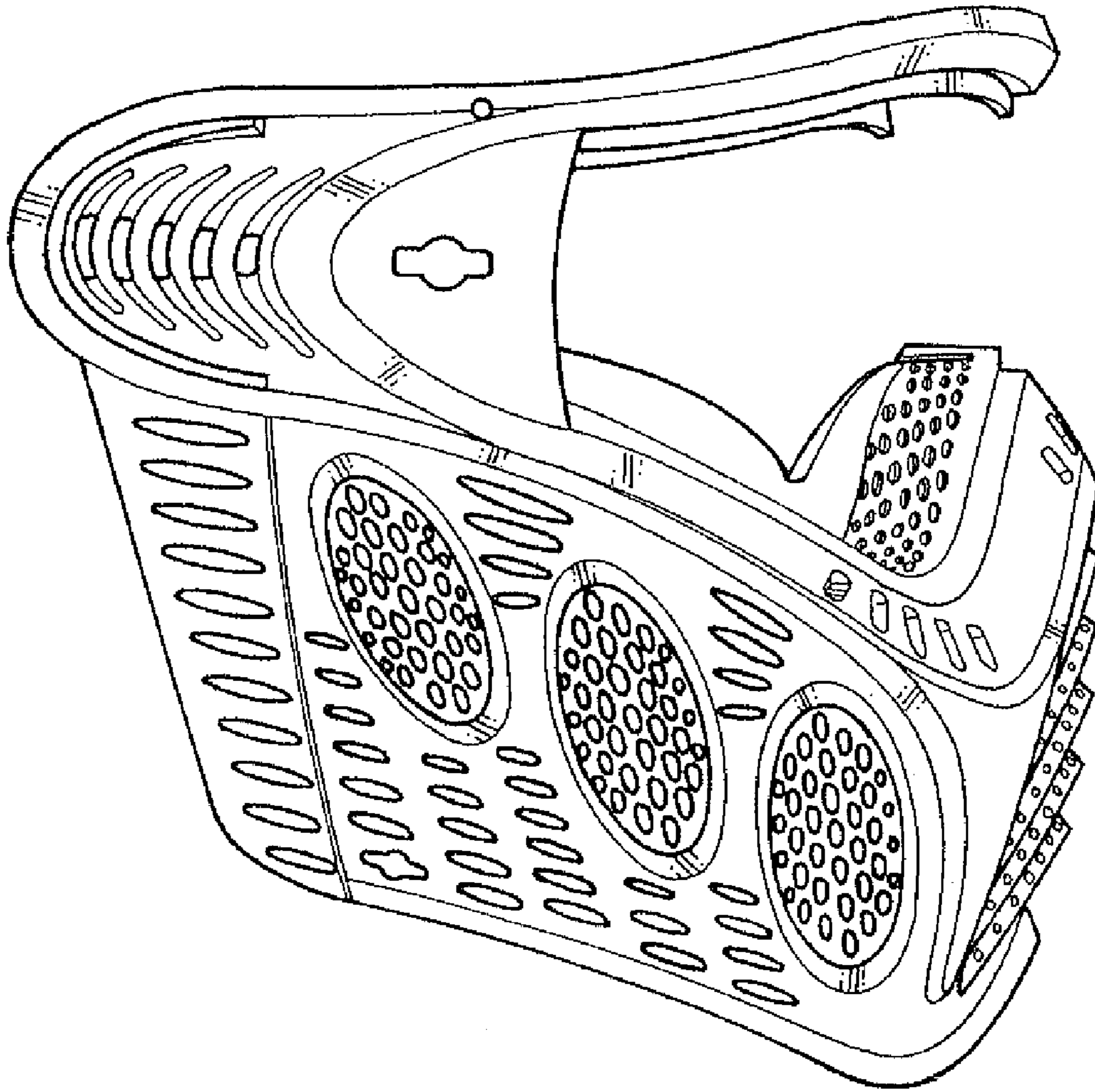


FIG.4

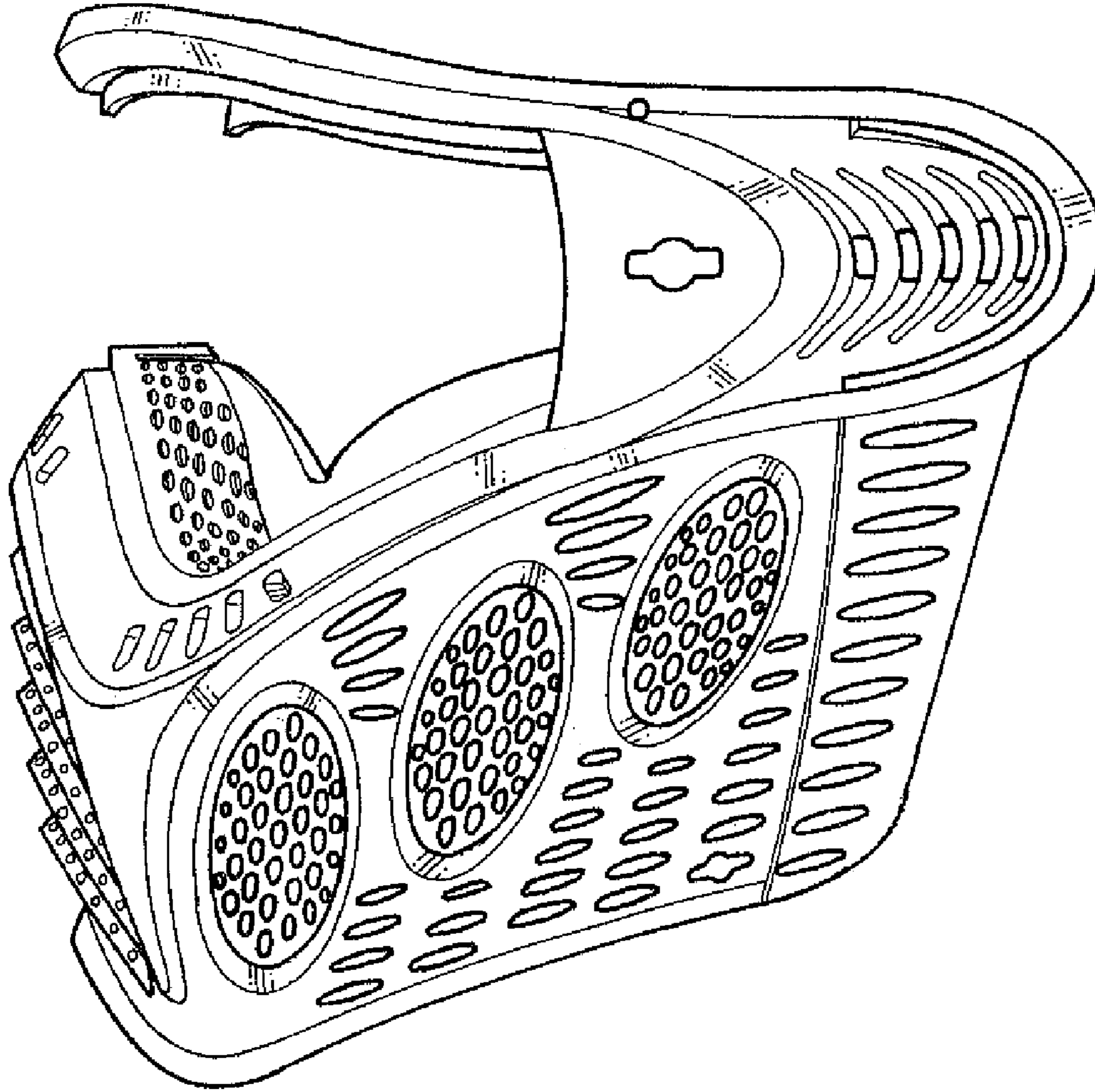


FIG.5

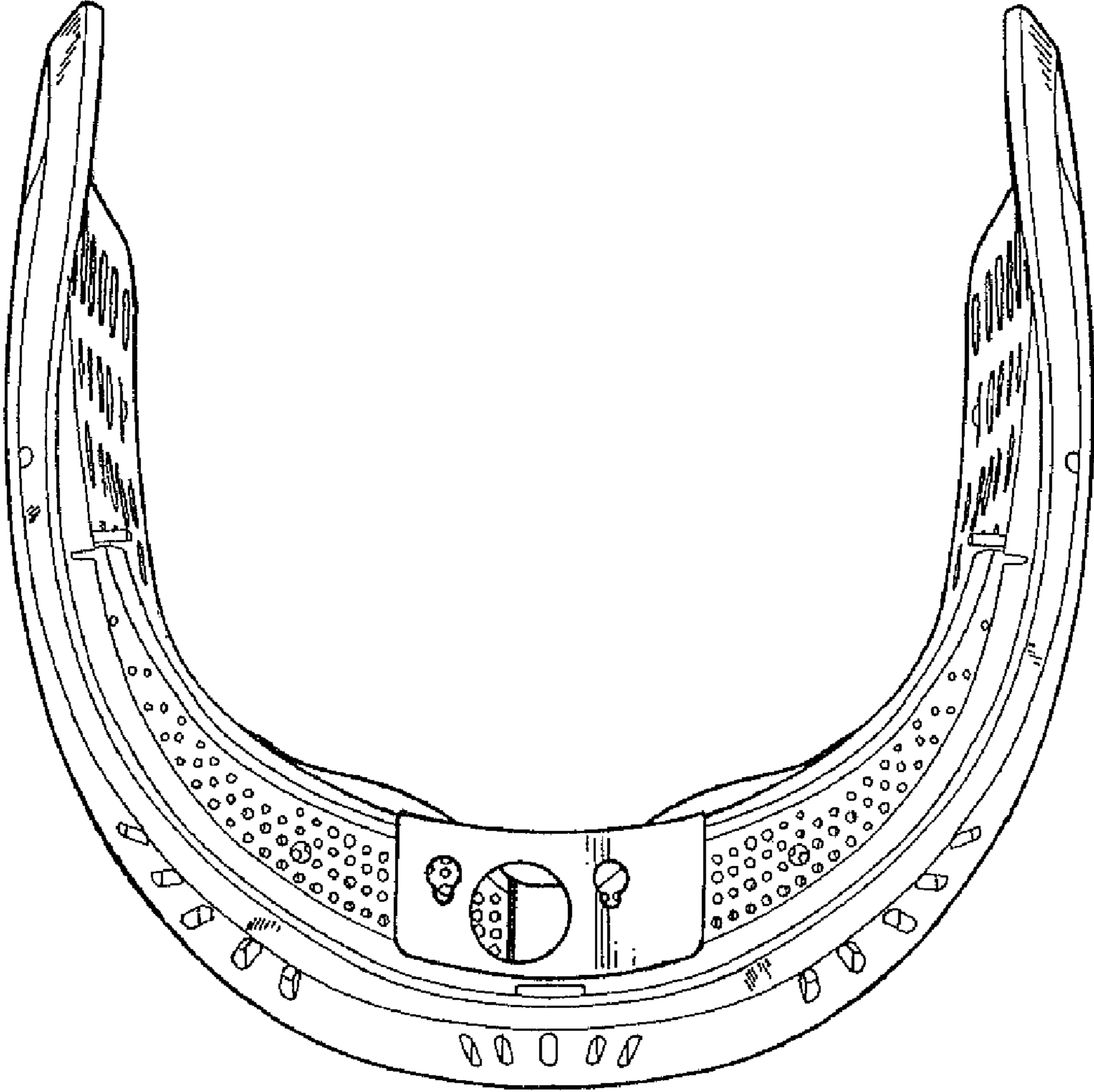


FIG.6

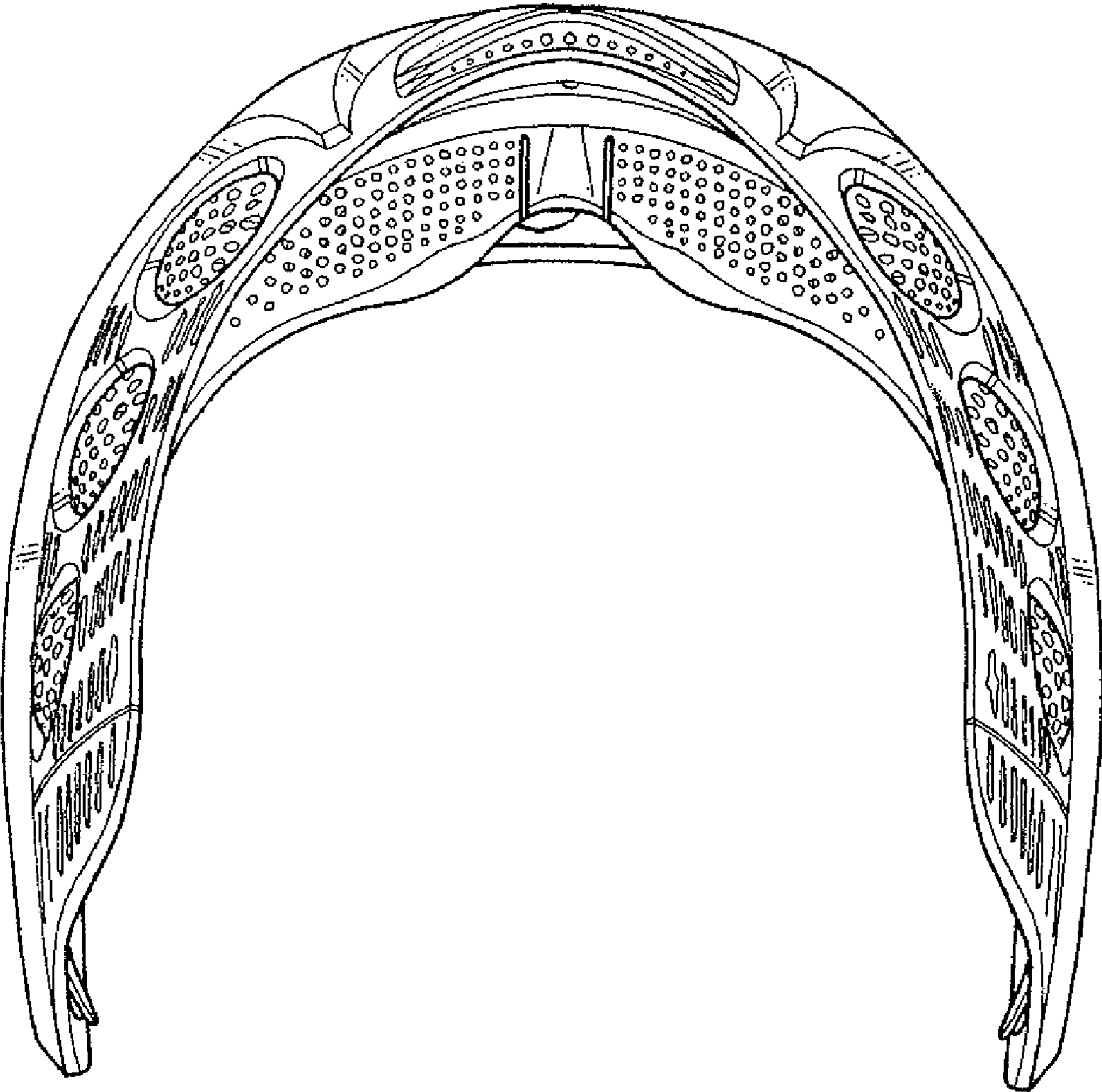


FIG.7